

Vacuum ▶ PVD Thin films ▶ Leak testing ▶ Plasma



Thin films sputtering system

DP 650



by

allianceconcept

Modular and evolutive system for multi layers and materials deposition.

Versatile Magnetron sputtering equipment, the DP650 has a chamber diameter of 650 mm. This volume can accommodate for example **four 200 mm diameter sources or six 100 mm.**

Benefiting from the best of joint developments of our sputtering system product line, the DP650 is currently our flagship product. We have supplied dozens of them around the globe, and as such, it is the spearhead of the PVD product range. Either used for industrial applications or R&D themes, DP650 is the right tool.

"The hallmarks of this best-seller are reliability, robustness and moreover, cost effectiveness."



Main features

Vacuum chamber diameter :	650 mm
Height :	320 mm
Volume :	About 110 litres
Ultimate vacuum (turbomolecular configuration) :	$5 \cdot 10^{-7}$ mbar ^[1]
Ultimate vacuum (cryogenic configuration) :	$5 \cdot 10^{-8}$ mbar ^[1]
System throughput :	6 active 100 mm position
Planar configuration uniformity :	< +/- 5% ^[1]
Through the wall installation :	Yes
Load lock :	Yes
Fully automatic system controller :	- Process management - Traceability

^[1] These values have been measured on equipment we have delivered and should be handled as information only. The features of a system depend on its final configuration.

